

LIST OF REFERENCES CITED BY APPLICANT

APPLICANT:

BRUNNER ET AL - 1

(Use several sheets if necessary)

FILING DATE: Oct. 22, 1999

GROUP: 1765

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
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	AH						
	AI						
	AJ						
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FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
C.B.	AL	0701275	03/13/96	EUROPE	H01L	21/306		
	AM							
	AN							
	AO							
	AP							

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)

C.B.	AR		Abstract for JP 4-26 120 F
C.B.	AS		Abstract 1765494 L 1983:45 13399 for Proceedings of the second Int. Symp. on Cleaning Techn. in Semiconductor Device Manufacturing, Electrochem. Soc., 1992 pp. 18-25
C.B.	AT		M. Meuris et al., Solid State Technologie, July 95, p 109

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Charlotte A. Buehn

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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

FORM PTO-1449
(REV. 7-80)

U.S. DEPARTMENT OF COMMERCE
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ATTY. DOCKET NO.: *ST9822*

SERIAL NO. 09/425,694

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APPLICANT: *Brunner et al-1*

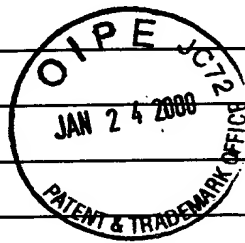
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U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
<i>C.B.</i>	AA	<i>5 803 980</i>	<i>09/08/98</i>	<i>Pas et al.</i>			
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FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO
<i>C.B.</i>	AL	<i>0731 495</i>	<i>09/11/96</i>	<i>Europe</i>			
<i>C.B.</i>	AM	<i>0844 650</i>	<i>05/24/98</i>	<i>Europe</i>			
<i>C.B.</i>	AN	<i>0731 498</i>	<i>09/11/96</i>	<i>Europe</i>			
<i>C.B.</i>	AO	<i>0859 404</i>	<i>08/19/98</i>	<i>Europe</i>			
	AP						

TECHNICAL MAIL ROOM

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OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)

<i>C.B.</i>	AR	<i>Patent Abstracts of Japan, vol. 1996, no. 06, June 28, 1996</i>
		<i>& JP 08 031837A (Mitsubishi Materials Silicon Corp;</i>
<i>C.B.</i>	AS	<i>Others: 01), February 2, 1996</i>
		<i>Meuris M et al: "The IMEC Clean: A New Concept For</i>
<i>C.B.</i>	AT	<i>Particle And Metal Removal On Si Surfaces", Solid</i>
		<i>State Technology, US, Cowan Publ. Corp. Washington</i>

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Charles A. Brown

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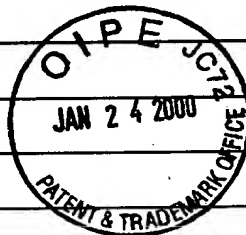
(Use several sheets if necessary)

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	AO						
	AP						

TC 1700 MAIL ROOM

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OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)

C.B.	AR		vol. 38, no. 7, 1995, p. 109-110, 112, 114
			XP 000523398, ISSN: 0038-111X, p. 110,
C.B.	AS		L. 5-44
			The English Derwent Abstract 1996-404246 [41]
	AT		comesp. to EP 0 731 495 A2 is enclosed

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